RUFULL (Russian Patents Full-Text)

File Subject Coverage	All patent-relevant areas of science and technology, i.e., all classes of the International Patent Classification
File Type	Full-text

Features

Thesauri	International Patent Classification (/IPC), Cooperative Patent Classification (/CPC)		
Alerts (SDIs)	Weekly or monthly (weekly is the default)		
CAS Registry Number® Identifiers	☐	SLART	☑
Keep & Share	☑	Structures	☐

Record Content

- Database records comprise all documents published for one application. Records contain bibliographic data including patent applicant, inventor, and agent data, patent, application, priority, and related application data, IPC, CPC, and EPO/ICO classification codes, abstract, and full-text of description and claims.
- Standardized and normalized patent assignee names are searchable in their own fields /PAS and /PAN.
- Numeric values of 59 physical and chemical properties are searchable in about 20,000 variants of the base and additional units within all full text fields in English.
- Key terms, indexed and displayed in the field /KT, enhance retrieval of relevant results, and make the evaluation of results more efficient. They are useful to broaden search scope more precisely than basic index searches.
- Some of the full-text has been created by Optical Character Recognition (OCR) software. Therefore, a small number of characters may have been misinterpreted, or portions of the text may have been incompletely recognized.

File Size

- Russia: More than 1.14 million family records with more than 1.52 million publications; EAPO: More than 60,000 family records with more than 100,000 publications; Soviet Union: More than 1.42 million family records (08/2021)

Coverage

Full-text of patent applications, granted patents and utility models published by

- Federal Service for Intellectual Property in Russia (Rospatent) since 1992
- Eurasian Patent Organization (EAPO) since 1996
- State Committee for Inventions and Discoveries of the former Soviet Union (Goskomizobretenie) from 1924 to 1992

Updates

- Weekly updates including IPC and CPC
- New records are available from Rospatent about six days after publication date with the complete content and from EAPO about nine days after publication date.

Language

- English
- Abstracts, detailed descriptions and claims are machine translated to English or from equivalent documents, titles are human translated.

Database Producer

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Email: helpdesk@fiz-karlsruhe.de

Sources

Patent applications, granted patents, and utility models by the Federal Service for Intellectual Property in Russia (Rospatent), by the Eurasian Patent Organization (EAPO), and by the State Committee for Inventions and Discoveries of the former Soviet Union (Goskomizobretenie)

User Aids

- Online Helps (HELP DIRECTORY lists all help messages available)
- Help for numeric property search: HELP NPS
- Help for key terms: HELP KEY TERMS
- Help for normalized patent assignee names: HELP PAN
- STNGUIDE

Cluster

- AEROTECH
- ALLBIB
- AUTHORS
- CORPSOURCE
- ENGINEERING
- FULLTEXT
- HPATENTS
- NPS
- PATENTS
- PNTTEXT

STN Database Clusters information:
http://www.stn-international.com/en/customersupport/customer-support#cluster+%7C+subjects+%7C+features

Search and Display Field Codes

If multiple search terms are linked with the AND-operator, all terms are searched in the complete database record, i.e. in all publications referring to one application. For a search in a specific publication of the record, connect the search term and the patent kind code with the (L)-proximity operator, e.g. S BOREHOLE/AB,TI,CLM (L) RUA/PK limits the search to Russian applications RUA.

Fields that allow left truncation are indicated by an asterisk (*).

General Search Fields

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index* (contains single words from title (TIEN), abstract (AB), detailed description (DETD), claims (CLM), main claims (MCLM) fields), and keyterms (KT)	None or /BI	S TRANSISTOR AND ELECTRODE S ACOUSTIC SENSOR S ?TRANSFER?	TIEN, AB, ABEN, DETD, DETDEN, CLM, CLMEN, MCLM, MCLMEN, KT
Abstract*	/AB, /ABEN	S BOREHOLE/AB	AB
Accession Number	/AN	S 599999/AN	AN
Agent	/AG	S TOMSKAJA ELENA VLADIMIROVNA/AG	AG
Application Country (WIPO code and text)	/AC	S EA/AC	AI
Application Date **(1)**	/AD	S AD=JAN 2011	AI
Application Number **(2)**	/AP (or /APPS)	S RU 2014-123503/AP	AI
Application Number, Original	/APO	S RU2014123503/15/APO	APO
Application Year **(1)**	/AY	S AY>=2005	AI
Claims*	/CLM	S DERIVATION/CLMS	CLM
Claims (English)	/CLMEN	S DERIVATION/CLMEN	CLMEN, CLM
Cooperative Patent Classification **(3)**	/CPC	S C12N0009/CPC	CPC
Cooperative Patent Classification, Action Date	/CPC.ACD	S 20121113/CPC.ACD	CPC.TAB
Cooperative Patent Classification, Keyword	/CPC.KW	S C12N0009/CPC (S) I/CPC.KW	CPC.TAB
Cooperative Patent Classification, Version	/CPC.VER	S 20130101/CPC.VER	CPC.TAB
Data Entry Date **(1)**	/DED	S 20190930-20191031/DED	DED
Data Update Date **(1)**	/DUPD	S 20190827/DUPD	DUPD
Document Type (code and text)	/DT (or /TC)	S PATENT/DT	DT
Entry Date **(1)**	/ED	S ED=DEC 2013	ED
Entry Date of Fulltext **(1)**	/EDTX	S EDTX>20191130	EDTX
EPC, Keyword Terms	/EPC.KW	S B22F3-00/EPC.KW	EPC
European Patent Classification	/EPC	S A01B0001-02B/EPC	EPC
Field Availability	/FA	S AB/FA	FA
International Patent Classification (Version 1-8) (ICA, ICI, ICM, ICS, IPCI, IPCR) **(3)**	/IPC	S A01B0001-16/IPC	ICM, ICS, IPCI, IPCR
International Patent Classification (Version 1-7) (ICA, ICI, ICM, ICS)	/IC	S A47J051-06/IC	IC, ICM, ICS

General Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Inventor	/IN (or /AU)	S PARK A REUM/IN	IN
Inventor, Country (WIPO code and text)	/IN.CNY	S RU/IN.CNY	IN, IN.CNY
IPC, Action Date	/IPC.ACD	S 13 JAN 2006/IPC.ACD	IPC.TAB
IPC, Additional I	/IPCI	S B21B0001/IPCI	IPCI, IPCI
IPC, Index (complementary)	/ICI	S B29K105-08/ICI S A61K031:40/ICI	ICI, IC
IPC, Initial	/IPC.KW	S INITIAL/IPC.KW	IPC.TAB
IPC, Keyword Terms	/ICA (or /IPCA)	S F16H061-14/ICA	ICA, IC
IPC, Main	/ICM (or IPCM)	S B29B001-06/ICM	ICM, IC
IPC, Reclassified	/IPCR	S B21D0007-08/IPCR	IPCR, IPC
IPC, Reform	/IPC.REF	S A01B0001-16/IPC.REF	IPC.TAB
IPC, Secondary	/ICS (or IPCS)	S B29H003-00/ICS	ICS, IC
IPC, Version	/IPC.VER (or IC.VER)	S 7/IPC.VER	IPC.TAB
Key Terms	/KT	S (LASER (3A) SOURCE?)/KT	KT
Language (code and text)	/LA	S RU/LA	LA
Language, Filing (code and text)	/LAF	S RU/LAF	LAF
Main Claim*	/MCLM	S LASER/MCLM	MCLM
Main Claim (English)	/MCLMEN	S LASER/MCLMEN	MCLMEN
Number of Claims **(1)**	/CLMN	S 5-10/CLMN	CLMN
Number of Paragraphs in DETD (Detailed Description) **(1)**	/DETN	S 20-30/DETN	DETN
Patent Assignee**(4)**	/PA (or /CS)	S SAMSUNG/PA	PA
Patent Assignee, Country	/PA.CNY	S RU/PA.CNY	PA, PA.CNY
Patent Applicant Normalized	/PAN	S SAMSUNG/PAN	PAN
Patent Applicant Standardized	/PAS	S SAMSUNG AEROSPACE INDUSTRIES/PAS	PAS
Patent Country (WIPO code and text)	/PC	S EA/PC	PI
Patent Information Publication Type	/PIT	S RUA APPLICATION FOR INVENTION (PUBLISHED FROM 19921014)/PIT	PIT
Patent Kind Code	/PK	S RUA3/PK	PI
Patent Number **(2)**	/PN (or /PATS)	S EA2015091398/PN	PI
Patent Number, Original	/PNO	S RU2014123503/PNO	PNO
Patent Number/Kind Code	/PNK	S RU2733410 C2/PNK	PI
Physical Properties	/PHP	S PHV/PHP (S) BUFFER/BI	KWIC
Priority Country (WIPO code and text)	/PRC	S RU/PRC S KOREA, REPUBLIC OF/PRC	PRN
Priority Date **(1)**	/PRD	S PRD=MAY, 20 2003 S 20030520/PRD	PRN
Priority Date, First **(1)**	/PRDF	S 20010704/PRDF	PRN
Priority Number **(2)**	/PRN	S AT1982-2545/PRN	PRN
Priority Number, Original	/PRNO	S AT0100016/PRNO	PRNO, PRAO

General Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Priority Year **(1)**	/PRY	S 1999/PRY	PRN
Priority Year, First **(1)**	/PRYF	S 1999/PRYF	PRN
Publication Date **(1)**	/PD	S 19990108/PRD	PI
Publication Year **(1)**	/PY	S 2017/PY	PI
Related Patent Country	/RLC	S WO/RLC	RLI
Related Application Number	/RLN	S WO1982-JP96/RLN	RLI
Related Application Date **(1)**	/RLD	S 20120109/RLD	RLI
Related Application Type	/RLT	S PCT APPLICATION/RLT	RLI
Related Application Year **(1)**	/RLY	S 2017/RLY	RLI
Related Patent Number	/RLPN	S WO2000000071/RLPN	RLI
Title (English)*	/TI, /TIEN	S LASER/TI	TI, TIEN
Update Date **(1)**	/UP	S 20191113/UP	UP
Update Date Text **(1)**	/UPTX	S 20191030/UPTX	UPTX

(1) Numeric search field that may be searched using numeric operators or ranges.
(2) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(3) An online thesaurus is available in this field.
(4) Search with implied (S) proximity is available in this field.

Super Search Fields

Enter a super search code to execute a search in one or more fields that may contain the desired information. Super search fields facilitate crossfile and multifile searching. EXPAND may not be used with super search fields. Use EXPAND with the individual field codes instead.

Search Field Name	Search Code	Fields Searched	Search Examples	Display Codes
Application Number Group	/APPS	AP, PRN	S RU2017-117295 APPS	AI, PRAI, APPS
Patent Assignee Group	/PASS	PA, PA.T, PAS, PAN	S SAMSUNG/PASS	PA, PAS, PAN, PASS
Patent Number Group	/PATS	PN, RLPN	S RU2747967/PATS	PN, RLPN, PATS

Property Fields[1)]

In RUFULL a numeric search for a specific set of physical properties (/PHP) is available within the full-text fields (TI, AB, DETD, CLM, BI). The numeric values are not displayed as single fields, but highlighted within the hit displays.

Use EXPAND/PHP to search for all available physical properties. A search with the respective field codes will be carried out in all database fields with English text. The /PHP index contains a complete list of codes and related text for all physical properties available for numeric search.

Field Code	Property	Unit	Symbol	Search Examples
/AOS	Amount of substance	Mol	mol	S 10 /AOS
/BIR	Bit Rate	Bit/Second	bit/s	S 8000-10000/BIR
/BIT	Stored Information	Bit	Bit	S BIT > 3 MEGABIT
/CAP	Capacitance	Farad	F	S 1-10 MF/CAP
/CATA	Catalytic Activity	Katal	kat	S 1-10/KATA
/CDN	Current Density	Ampere/Square Meter	A/m^2	S CDN>10 A/M**2
/CMOL	Molarity, Molar Concentration	Mol/Liter	mol/L	S UREA/BI (S) 8/CMOL
/CON	Conductance	Siemens	S	S 1S-3/CON
/DB	Decibel	Decibel	dB	S DB>50
/DEG	Degree	Degree	°	S CYLINDER/BI (S) 45/DEG
/DEN (/C)	Density (Mass Concentration	Kilogram/Cubic Meter	kg/m^3	S 5E-3-10E-3/DEN
/DEQ	Dose Equivalent	Sievert	Sv	S 100/DEQ
/DOA	Dosage	Milligram/Kilogram/Day	mg/kg/day	S 300/DOA
/DOS (/LD50)	Dosage	Milligram/Kilogram	mg/kg	S DOS>0.8
/DV	Viscosity, dynamic	Pascal * Second	Pa * s	S DV>5000
/ECH (/CHA)	Electric Charge	Coulomb	C	S 0.0001-0.001/ECH
/ECO (/ECND)	Electrical Conductivity	Siemens/Meter	S/m	S ECO>800 S/M (15A) AQUEOUS
/ELC (/ECC)	Electric Current	Ampere	A	S 1-10/ELC
/ELF (/ECF)	Electric Field	Volt/Meter	V/m	S 200/ELF
/ENE	Energy	Joule	J	S DROPLETS (10A) 40 JOULE - 70 JOULE /ENE
/ERE (/ERES)	Electrical Resistivity	Ohm * Meter	Ohm * m	S ERE>0.1
/FOR	Force	Newton	N	S 50 N /FOR
/FRE (/F)	Frequency	Hertz	Hz	S OSCILLAT?/BI (S) 1- 3/FRE
/IU	International Unit	none	IU	S IU>1000 (P) VITAMIN A
/KV	Viscosity, kinematic	Square Meter/Second	m^2/s	S METHYLPOLYSILOXANES/BI (10A) 200-300 CST /KV
/LEN (/SIZ)	Length, Size	Meter	m	S 1-4/LEN
/LUME	Luminous Emittance, Illuminance	Lux	lx	S 10-50/LUME
/LUMF	Luminous Flux	Lumen	Lm	S LUMF>1000
/LUMI	Luminous Intensity	Candela	cd	S LUMI<4
/M	Mass	Kilogram	kg	S ALLOY/BI (30A) 1E-10-1E-5/M
/MCH	Mass to Charge Ratio	none	m/z	S MCH=1

Property Fields[1] (cont'd)

Field Code	Property	Unit	Symbol	Search Examples
/MFD (/MFS)	Magnetic Flux Density	Tesla	T	S MFD>102
/MFR (/MFL)	Mass Flow Rate	Kilogram/Second	kg/s	S MFR<0.1
/MFST	Magnetic Field Strength	Ampere/Meter	A/m	S MFST/PHP
/MM (/MW, /MOM)	Molar Mass	Gram/Mol	g/mol	S 2000-3000 G/MOL/MM
/MOLS	Molality of Substance	Mol/Kilogram	mol/kg	S 01.-10 MOL/KG/MOLS
/MVR	Melt Volume Rate, Melt Flow Rate	none	g/10 min	S 3/MVR
/PER	Percent (Proportionality)	none	%	S POLYMER?/AB (5A) 4/PER
/PHV (/PH)	pH Value	pH	pH	S 7.4-7.6/PHV
/POW (/PW)	Power	Watt	W	S "HG-XE-?"/BI (S) 100-200 WATT/POW
/PPM	Parts per million	Ppm	ppm	S 100 PPM /PPM (10A) ADDITIVE/BI
/PRES (/P)	Pressure	Pascal	Pa	S (VACUUM (5A) DISTILL?)/BI (S) 1000-1100/PRES
/RAD	Radioactivity	Becquerel	Bq	S RAD/PHP
/RES	Electrical Resistance	Ohm	Ohm	S SENSOR /BI (S) 10- 100/RES
/RI	Refractive Index	none		S 3-4/RI
/RSP	Rotational Speed	Revolution/Minute	rpm	S 2 RPM - 100 RPM /RSP (S) ENGINE/BI
/SAR	Area /Surface Area	Square Meter	m^2	S PLATE/BI (S) 10 M**2 - 100 M**2 /SAR
/SOL (/SLB)	Solubility	Gram/100 gram	g/100 g	S SOL>20 G/100G (5A) WATER
/SSAM	Specific Surface Area, Mass	Square Meter/ Kilogram	m2/kg	S 9/SSAM
/STSC (/ST)	Surface Tension	Joule /Square Meter	J/m^2	S 60 J/M**2/STSC
/TCO (/TCND)	Thermal Conductivity	Watt/Meter * Kelvin	W/m * K	S 1/TCO (S) HEAT?
/TEMP (/T)	Temperature	Kelvin	K	S 20-25/TEMP
/TEX	Tex	Gram/Kilometer	g/km	S 1-5/TEX
/TIM	Time	Second	s	S ?INCUB?/BI (10A) 50 S - 150 S /TIM
/VEL (/V)	Velocity	Meter per Second	m/s	S REDUC?/BI (S) 1E-3-5E-3/VEL
/VELA	Velocity, angular	Radian/Second	rad/s	S VELA>10
/VLR	Volumetric Flow Rate	Cubic Meter/Second	m^3/s	S 1 M**3/S - 2 M**3/S /VLR (S) ABRASIVE
/VOL	Volume	Cubic Meter	m^3	S 1E-8-2E-8/VOL.EX
/VOLT	Voltage	Volt	V	S TENSION/BI (10A) 5E-3 V <VOLT<7E-3 V

(1) Exponential format is recommended for the search of particularly high or low values, e.g. 1.8E+7 or 1.8E7 (for 18000000) or 9.2E-8 (for 0.000000092).

International Patent Classification (/IPC) Thesaurus

The classifications, validity and catchwords for the main headings and subheadings from the current (8th) edition of the WIPO International Patent Classification (IPC) manual are available. The classifications from the previous editions (1-7) are also available as separate thesauri. To EXPAND and SEARCH in the thesauri for editions 1–7, use the field code followed by the edition number, e.g., /IPC2, for the 2nd edition. Catchwords are included only in the thesauri for the 8th, 7th, 6th, and 5th editions.

Code	Content	Examples
ADVANCED (ADV)	Advanced Codes for the Core Level IPC Code	E A61K0006-06+ADVANCED/IPC
ALL	All Associated Terms (BT, SELF, NT, RT)	E C01C003-00+ALL/IPC
BRO (MAN)	Complete Class	E C01C+BRO/IPC
BT	Broader Term (BT, SELF)	E C01F001-00+BT/IPC
CORE (COR)	Core Codes for the Advanced Level IPC Code	E G08C0019-22+CORE/IPC
ED	Complete title of the SELF term and IPC manual edition	E C01F001-00+ED/IPC
HIE	Hierarchy Term (Broader and Narrower Term) (BT, SELF, NT)	E C01B003-00+HIE/IPC
INDEX	Complete title of the SELF term	E C01F001-00+INDEX/IPC
KT	Keyword Term (catchwords) (SELF, KT)	E CYANOGEN+KT/IPC
NEXT	Next Classification	E C01C001-00+NEXT5/IPC
NT	Narrower Terms (SELF, NT)	E C01C+NT/IPC
PREV	Previous Classification	E C01C001-12+PREV10/IPC
RT (SIB)	Related Terms (SELF, RT)	E C01C003-20+RT/IPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E C01F001-00+TI/IPC

CPC Thesaurus

This thesaurus is available in the /CPC search field. All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL	All usually required terms (BT, SELF, CODE, DEF)	E C12M0001-005+ALL/CPC
AUTO **(1)**	Automatic relationship (BT, SELF, CODE, DEF)	E G01J003-443+AUTO/CPC
BT	Broader terms (BT, SELF)	E G01J0003-443+BT/CPC
CODE	Classification Code (SELF, CODE)	E CARTRIDGES+CODE/CPC
DEF	Definition (SELF, DEF)	E B65G0045-16+DEF/CPC
HIE	Hierarchy terms (all broader and narrower terms) (BT, SELF, DEF, NT)	E A01B0001+HIE/CPC
KT	Keyword terms (SELF, KT)	E LASER+KT/CPC
MAX	All associated terms	E G01J0003-44+MAX/CPC
NEXT	Next classification within the same class (SELF, NEXT)	E A01B0001-24+NEXT/CPC
NEXT(n)	Next n classification within the same class	E A01B0001-24+NEXT3/CPC
NT	Narrower terms	E G05B0001-04+NT/CPC
PREV	Previous Code within the same class (SELF, PREV)	E G05B0019-00+PREV/CPC
PREV(n)	Previous n classifications within the same class	E G05B0019-00+PREV2/CPC
TI	Complete Title of SELF Term and Broader Terms (BT, SELF)	E G05B0001-03+TI/CPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON, the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

DISPLAY and PRINT Formats

Any combination of formats may be used to display or print answers. Multiple codes must be separated by spaces or commas, e.g., D L1 1-5 TI PA. The fields are displayed or printed in the order requested.

The information of the latest publication is displayed by default. To display the content for all levels of the record you can combine all display fields and formats with the qualifier .M except FA, SCAN, and TRIAL.

For displaying a particular publication of a database record, you can simply add for certain display field the kind code to the appropriate display format, e.g. ALL.A. Fields that allow this are indicated by a number (3).

Hit-term highlighting is available for all fields. Highlighting must be ON during SEARCH to use the HIT, KWIC, and OCC formats.

The default display format is STD.M, i.e., all publication levels of one family in the STD format.

Format	Content	Examples
AB (ABS)	Abstract	D TI AB 1-5
ABEN	Abstract (English)	D ABEN
AI (AP) **(1)**	Application Information	D AI
AG	Agent	D AG
AN	Accession Number	D L3 AN
CLM **(3)**	Claims	D CLM
CLMEN	Claims (English)	D CLMEN
CLMN **(2)**	Number of Claims	D CLMN
CPC	Cooperative Patent Classification	D CPC
CPC.TAB	CPC, Tabular	CPC.TAB
DETD **(3)**	Detailed Description	D DETD
DETDEN	Detailed Description (English)	D DETDEN
DETN **(2)**	Number of Paragraphs in DETD	D DETN
DT (TC)	Document Type	D DT
ED	Entry Date	D ED
EDP	Entry Date Patent	D EDP
EDTX	Entry Date of Fulltext	D EDTX
EPC	European Patent Classification	D EPC
FA	Field Availability (for all publication levels)	D FA
IC	IPC (format contains ICA, ICI, ICM, ICS)	D IC
ICA	IPC, Additional	D ICA
ICI	IPC, Index	D ICA
ICM	IPC, Main	D IC
ICO	In-Computer-only Classification	D ICO
ICS	IPC, Secondary	D ICS
IN (AU)	Inventor (in English)	D IN
IN.CNY	Inventor, Country	D IN.CNY
IPCI	IPC, Initial	D IPCI
IPCR	IPC, Reclassified	D IPCR
KT	Key Terms	D KT
LA	Language	D LA
LAF	Language of Filing	D LAF
MCLM	Main Claim	D MCLM
MCLMEN	Main Claim (in English)	D MCLMEN
PA (CS)	Patent Applicant/Patentee (in English)	D PA
PA.CNY	Patent Applicant, Country	D PA.CNY
PAN	Patent Applicant Normalized	D PAN
PAS	Patent Applicant Standardized	D PAS
PI (PN, PATS) **(1)**	Patent Information	D PI
PIT	Patent Information Publication Type	D PIT

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
PNO	Patent Number, Original Format	D PNO
PRN (PRAI) **(1,5)**	Priority Information	D PRN
PRNO (PRAO) **(2)**	Priority Number, Original Format	D PRNO
RLI (RLN)	Related Patent Information	D RLI
TIEN (TI)	Title (in English)	D TIEN
UP	Update Date	D UP
UPTX	Update Date Text	D UPTX
ALL **(1)**	AN, EDP, ED, UP, EDTX, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, LAF, LA, DT, PIT, PI, AI or APO (only if no AI), RLI, PRAI or PRAO (only if no PRAI), ICM, ICS, IPCI, IPCR, CPC, ABEN, DETDEN, CLMEN, KT	D ALL
IALL **(1)**	ALL, indented with text labels	D IALL
DALL **(1)**	ALL, delimited for post processing	D DALL
APPS **(1)**	AI, RLN, PRAI	D APPS
BIB **(1)**	AN, EDP, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, LAF, LA, DT, PIT, PI, AI, RLI, PRAI	D BIB
IBIB **(1)**	BIB, indented with text labels	D IBIB
BRIEF **(1)**	AN, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, ICM, ICS, IPCI, IPCR, CPC, ABEN, MCLMEN, KT	D BRIEF
IBRIEF **(1)**	BRIEF, indented with text labels	D IBRIEF
IND	ED, IPC (ICM, ICS, IPCI, IPCR), CPC	D IND
IPC	International Patent Classification (ICM, ICS, IPCI, IPCR)	D IPC
IPC.TAB	IPC, IPC.KW, IPC.VER, in tabular version	D IPC.TAB
CPC.TAB	CPC, in tabular version	D CPC.TAB
MAX (ALL.M) **(1)**	AN, EPD, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, AG, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, ICM, ICS, IPCI, IPCR, CPC, ABEN, DETDEN, CLMEN, KT, FA for all levels of publication	D MAX
IMAX (IALL.M) **(1)**	MAX, indented with text labels	D IMAX
SCAN **(4)**	TI (random display without answer numbers)	D SCAN
STD **(1)**	AN, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, AG, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, ICM, ICS, IPCI, IPCR, CPC (STD.M is default)	D STD
ISTD **(1)**	STD, indented with text labels	D ISTD
TRIAL (TRI, SAM, SAMPLE, FREE)	ED, EDTX, UP, UPTX, TIEN, FA, DETN, CLMN	D TRIAL
TX	DETDEN, CLMEN	D TX
HIT	Hit term(s) and field(s)	D HIT
KWIC	Up to 50 words before and after hit term(s) (KeyWord-In-Context)	D KWIC
OCC	Number of occurrences of hit term(s) and field(s) in which they occur	D OCC

(1) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(2) Custom display only.
(3) You can combine this display field with the qualifier .PK (Patent Kind Code) to display the content for a certain publication level of a record, e.g. CLM.B2.
(4) SCAN must be specified on the command line, i.e., D SCAN or DISPLAY SCAN.
(5) If priority information is not available for a certain document, this information is taken from the application information of this document and marked with an asterisk (*).

SELECT, ANALYZE, and SORT Fields

The SELECT command is used to create E-numbers containing terms taken from the specified field(s) in an answer set.

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The SORT command is used to rearrange the search results in either alphabetic or numeric order of the specified field(s).

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Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Accession Number	AN	Y	Y
Application Country	AC	Y	Y
Application Date	AD	Y	Y
Application Information	AI (AP, APPS)	Y **(2)**	Y
Application Number, Original	APO	Y	N
Application Year	AY	Y	Y
CPC Classification	CPC	Y	Y
Document Type	DT	Y	Y
Entry Date	ED	Y	Y
Entry Date Full-Text	EDTX	Y	Y
EPC	EPC	Y	Y
Field Availability	FA	Y	N
ICO	ICO	Y	Y
International Patent Classification	IC	Y	N
Inventor	IN (AU)	Y	Y
Inventor, Country	IN.CNY	Y	Y
IPC (ICM, ICS, IPCI, IPCR)	IPC	Y	Y
IPC, Additional	IPC.A	Y **(3)**	N
IPC, Advanced Level Symbols	ICA	Y	Y
IPC, Advanced Level Symbols for Invention	IPC.AI	Y **(3)**	N
IPC. Index	ICI	Y	Y
IPC, Initial	IPCI	Y	Y
IPC, Main	ICM	Y	Y
IPC, Reclassified	IPCR	Y	Y
IPC, Reform	IPC.REF	Y	N
IPC, Secondary	ICS	Y	Y
Key Terms	KT	Y	N
Language	LA	Y	Y
Language of Filing	LAF	Y	Y
Number of Paragraphs in DETD	DETN	N	Y
Occurrence Count of Hit Terms	OCC	N	Y
Patent Assignee/Patentee	PA (CS)	Y	Y
Patent Assignee, Country	PA.CNY	Y	Y
Patent Applicant Normalized	PAN	Y	Y
Patent Applicant Standardized	PAS	Y	Y
Patent Country	PC	Y	Y
Patent Information Publication Type	PIT	Y	Y
Patent Kind Code	PK	Y	Y
Patent Number	PI (PN, PATS)	Y (default)	Y
Patent Number, Original	PNO	Y	Y
Patent Number/Kind Code	PNK	Y	Y
Pre-IPC8 Symbols from ICM and first IPC8 values from 2006-present	IPC.F	Y **(3)**	Y

SELECT, ANALYZE, and SORT Fields (cont'd)

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Priority Date	PRD	Y	Y
Priority Date, First	PRDF	Y	Y
Priority Number	PRN (PRAI)	Y	Y
Priority Number, Original	PRNO	Y	Y
Priority Year	PRY	Y	Y
Priority Year, First	PRYF	Y	Y
Publication Date	PD	Y	Y
Publication Year	PY	Y	Y
Related Patent Country	RLC	Y	Y
Related Application Number	RLN	Y	Y
Related Application Date	RLD	Y	Y
Related Application Type	RLT	Y	Y
Related Application Year	RLY	Y	Y
Related Patent Date	RLPD	Y	Y
Related Patent Number	RLPN	Y	Y
Related Patent Year	RLPY	Y	Y
Title	TIEN	Y	Y
Update Date	UP	Y	Y
Update Date Text	UPTX	Y	Y

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g., SEL HIT TI.
(2) Selects or analyzes application numbers with /AP appended to the terms created by SELECT.
(3) Appends /IPC to the terms created by SELECT.

Sample Records

DISPLAY BIB

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AN      305449   RUFULL EDP 20210727  ED 20210727 UP 20210727 EDTX 20210727
        DED 20120820 DUPD 20181016
TIEN    N-OXYCARBONYL-SUBSTITUTED 5-DEOXY-5-FLUOROCYTIDINES AND PHARMACEUTICAL
        FORMULATION
IN      ARASAKI Motokhiro, JP
        IShITSUKA Khideo, JP
        KURUMA Isami, JP
        MIVA Masanori, JP
        MURASAKI Chikako, JP
        ShIMMA Nobuo, JP
        UMEDA Isao, JP
PA      F.KhOFFMANN-LJa ROSh AG
PAS     F.KHOFFMANN LJA ROSH
LAF     Russian
LA      Russian
DT      Patent; (Fulltext)
PI      RU 2458932               C2    20120820
PIT     RUC2 PATENT FOR INVENTION (2ND PUBL.) [FROM NO. 2000001 ONWARDS]
AI      RU 1993-56196                  19931216
PRAI    EP 1992-121538                 19921218ISTD.MS
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ENTRY DATE PATENT:      20210727
ENTRY DATE:             20210727
UPDATE DATE:            20210727
ENTRY DATE (FULLTEXT):  20210727
DATA ENTRY DATE:        20141016
DATA UPDATE DATE:       20200107
TITLE (ENGLISH):        PHARMACEUTICAL COMPOSITION, CONTAINING
                        FITOKANNABINOIDYKANNABIDIVARIN (CBDV) AND KANNABIDIOL
                        (CBD)
LANGUAGE OF FILING:     English
LANGUAGE OF PUBL.:      Russian
DOCUMENT TYPE:          Patent; (Fulltext)
PATENT INFORMATION:     EA 2014090711         A1      20140930
PATENT INFORMATION TYPE:EAA1 PUBLICATION OF APPLICATION WITH SEARCH REPORT
APPLICATION INFO.:      EA 2014-90711         A       20120914
PRIORITY INFO.:         GB 2011-16789                 20110929
                        WO 2012-GB52284               20120914
RELATED PATENT INFO.:   WO 2013045891                 20130404
RELATED DOC. INFO.:     WO 2012-GB52284               20120914   PCT
                        Application
IPC ORIGINAL:           A61K0031-05 [I,A]; A61K0031-352 [I,A]; A61K0036-185
                        [I,A]; A61K0045-06 [I,A]; A61P0025-08 [I,A]
CPC CLASSIF.:           A61K0031-352;  A61K0031-045;  A61K0031-353;
                        A61K0045-06;  A61K0031-05;  A61K0036-185

ACCESSION NUMBER:       1853211   RUFULL
ENTRY DATE PATENT:      20210727
ENTRY DATE:             20210727
UPDATE DATE:            20210727
ENTRY DATE (FULLTEXT):  20210727
DATA ENTRY DATE:        20180308
DATA UPDATE DATE:       20200107
TITLE (ENGLISH):        PHARMACEUTICAL COMPOSITION, CONTAINING
                        FITOKANNABINOIDYKANNABIDIVARIN (CBDV) AND KANNABIDIOL
                        (SYDNEY)
LANGUAGE OF FILING:     English
LANGUAGE OF PUBL.:      Russian
DOCUMENT TYPE:          Patent; (Fulltext)
PATENT INFORMATION:     EA 2014090711         A8      20180228
PATENT INFORMATION TYPE:EAA8 MODIFIED FIRST PAGE [FROM 20120101 ONWARDS]
APPLICATION INFO.:      EA 2014-90711         A       20120914
PRIORITY INFO.:         GB 2011-16789                 20110929
                        WO 2012-GB52284               20120914
RELATED PATENT INFO.:   WO 2013045891                 20130404
RELATED DOC. INFO.:     WO 2012-GB52284               20120914   PCT
                        Application
IPC ORIGINAL:           A61K0031-05 [I,A]; A61K0031-352 [I,A]; A61K0036-185
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                        A61K0045-06;  A61K0031-05;  A61K0036-185

ACCESSION NUMBER:       1853211   RUFULL
ENTRY DATE PATENT:      20210727
ENTRY DATE:             20210727
UPDATE DATE:            20210727
ENTRY DATE (FULLTEXT):  20210727
DATA ENTRY DATE:        20180614
DATA UPDATE DATE:       20200107
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RUFULL

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TITLE (ENGLISH):          PHARMACEUTICAL COMPOSITION COMPRISING THE
                          PHYTOCANNABINOIDS CANNABIDIVARIN (CBDV) AND CANNABIDIOL
                          (CBD)
PATENT APPLICANT(S):      GW PHARMA LTD
                          OTSUKA PHARMA CO LTD
PATENT APPL. STANDARD.: GW PHARMA; OTSUKA PHARMA
PATENT APPL. NORMAL.:     OTSUKA
LANGUAGE OF FILING:       English
LANGUAGE OF PUBL.:        Russian
DOCUMENT TYPE:            Patent; (Fulltext)
PATENT INFORMATION:       EA 29697              B1      20180531
PATENT INFORMATION TYPE:EAB1 PATENT
APPLICATION INFO.:        EA 2014-90711         A       20120914
PRIORITY INFO.:           GB 2011-16789                 20110929
                          WO 2012-GB52284               20120914
RELATED PATENT INFO.:     WO 2013045891                 20130404
RELATED DOC. INFO.:       WO 2012-GB52284               20120914   PCT
                          Application
IPC ORIGINAL:             A61K0031-05 [I,A]; A61K0031-352 [I,A]; A61K0036-185
                          [I,A]; A61K0045-06 [I,A]; A61P0025-08 [I,A]
CPC CLASSIF.:             A61K0031-352;  A61K0031-045;  A61K0031-353;
                          A61K0045-06;  A61K0031-05;  A61K0036-185
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DISPLAY ALL (STN format)

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AN     399838   RUFULL EDP 20210727  ED 20210727 UP 20210727 EDTX 20210727
       DUPD 20171101
TIEN   DEVICE FOR CRYOMASSAGE
IN     Gel'fgat David Mendelevich[RU]
       Skipidarov Sergej Jakovlevich[RU]
       Jakhats Majkl[US]
       Kamenskij Vjacheslav Tikhonovich[RU]
PA     Spetsializirovannoe konstruktorsko-tekhnologicheskoe bjuro "Nord"
       Spetsializirovannoe konstruktorsko-tekhnologicheskoe bjuro "Nord"
PAS    SPETSIALIZIROVANNOE KONSTRUKTORSKO TEKHNOLOGICHESKOE BJURO NORD;
       SPETSIALIZIROVANNOE KONSTRUKTORSKO TEKHNOLOGICHESKOE BJURO NORD
LAF    Russian
LA     Russian
DT     Patent; (Fulltext)
PI     RU 2047298              C1    19951110
PIT    RUC1 PATENT FOR INVENTION [FROM NO. 2000001 ONWARDS]
AI     RU 1993-31379           A     19930527
PRAI   RU 1993-31379                 19930527
ICM    A61H0007-00 (6)
ICS    F25B0001-02 (6)
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IPCR   A61F0007-00 [I,A]; A61F0007-02 [I,A]; F25B0021-04 [N,A]
CPC    A61F2007-0003;  A61F2007-0296;  A61F2007-0075;  A61F0007-007;
       F25B0021-04;  F25B2321-0251
EPC    A61F0007-00E
ICO    K61F0007-02T2; R25B0021-04; R25B0321-0251; K61F0007-00A2A; K61F0007-00E2

ABEN
       Original
       FIELD: physical therapy apparatus; cooling massage. SUBSTANCE: device
       has massage units 1 and 2, each unit has casing containing thermocontact
       plate, heat removal system and thermoelements. Unit for heating or
       cooling thermocontact plate includes direct current supply unit.
       Automatic contrast thermocycle unit is placed between direct current
       supply unit and switching member. EFFECT: enhanced effectiveness of
```

massage. 7 cl, 6 dwg

ABOL

Original

DETD

[DESC0001] The invention relates to medical equipment and can be used in devices for kriomassazha , mainly used in prophylactic or conducive at face skin massage in cosmetic purposes.

[DESC0002] Is known device for kriomassazha , containing massage unit, including body, in which there are installed: teplokontaktnaya plate, heat removal system and thermal members, and agent for heating or cooling thermocontact plate, including direct current source, connected through switching element to termoelementam. Known device is used predominantly for massage face skin, besides transfer from of heating to cooling is effected by means of switching of massazherom switching element.

[DESC0003] On Figure 1 is shown massage unit with articulated joint, formed surface of body; on Figure 2 massage unit with articulated joint, forming surface of heat removal system; on Figure 3 teplokontaktnaya plate with support element; on Figure 4 common type of device; on Figure 5 common type of device with members pressing, consisting of two identical parts; on Figure 6 unit-circuit electric part of device.

[DESC0004] Device for local skin massage has: massaging units 1 and 2, each of which includes thermal members, consisting of semiconductor branches electronic conductivity of 3 (n-type), semiconductor branches hole conductivity 4 (p-type of), connected at ends commutation bridges 5, electrically insulating interlayer 6 and 7, teplokontaktnuyu plate 8, system of heat sink 9, body 10, which can be made with convex spherical surface 11 ; holder, consisting of two parts 12 and 13, having central recess with spherical concave wall 14, electric terminals thermoelements 15 and 16, the heat removal system may be made with external spherical surface 17, teplokontaktnaya plate may be made with projection 18 over perimeter, on which is fixed the supporting element 19, in plate holder groove is made 20, in which at means of fixer 21 are fixed termination of elements 22 and 23 pressing, made in the form of arc-shaped springs, having shape of headband with arched central portion 24, having curvilinear groove 25, in which at means of fixer 26 is secured end of element pressing; element pressing may have second element, identical to the first and including arc-shaped of spring 27 and 28, central arc-shaped section 29 and retainer 30, and elements of pressing are provided with possibility of changing their mutual arrangement, which is secured retainer 31 ; direct current source 32, connected through switching element 33 to termoelementam , series-connected voltage stabilizer 34 and pulse generator 35 ; wherein the input voltage stabilizer via the connector 36 is connected to the output of the source of direct current 32.

[DESC0005] Teplokontaktnye plate 8 is made from materials, possessing high thermal conductivity, for example, from copper, aluminium, beryllium oxide or alyumoksidnoi ceramics, in case of realization teplokontaktnoi plate from beryllium oxide or alyumoksidnoi ceramics switching tire thermal elements 5 may directly pripaivatsya to metal layers, preliminarily applied on surface teplokontaktnoi plate. Body 10 preferably made from heat-insulating material, for example, from plastic, the outer surface of the body is made spherical 11, and center of sphere-" 0 (cm. figure 1) is placed in the geometric center of the

housing. Massaging units 1 and 2 is placed in the plates of the holder, each of which consists of two parts 12 and 13, interconnected screws or catches (it is not indicated), with plates is made with central recess, having concave spherical wall 14, curvature of which corresponds to curvature spherical surface of body 11, and at joining of the contact surfaces 11 and 14 form hinge connection. As source of direct current 32, providing power supply of thermoelements, can be used sources of various types, for example, batteries, galvanic elements, photoelectric battery and T. d. Series-connected voltage stabilizer 34, pulse generator 35 and switching element 33 form unit for automatic contrast thermal cycling, which allows in automatic mode cyclically raised and to decrease temperature teplokontaktnoi plate 8.

[DESC0006] Device for local skin massage operates as follows. Depending on size of a head of the user is adjusted distance between massage units 1 and 2, varying arrangement of end section of arched of spring 3 in curvilinear groove 25, and fixed its retainer 26, simultaneously is installed force of pressing teplokontaktnykh plates 8 to skin. Is adjusted placement of end sections arc-shaped springs 22 and 23 in slots 20 plates holder, setting thereby arrangement of teplokontaktnykh plates 8 in height (for example, setting their in temporal the area near termination of eyebrows) and secured retainer 21. Is additionally regulated length of arc-shaped springs 27 and 28 of the second element holder, trying to its tight fit to back of the. Thereby is increased reliability of fixation massage blocks 1 and 2, eliminating their possible movement in horizontal direction at action of mechanical loads. Regulators of automatic contrast thermal cycling (it is not indicated) is installed specified parameters of the mode of contrast thermal cycling: temperature of heating and cooling teplokontaktnykh plates 8, duration of the processes of cooling and heating (pulse duration), which can be choose in accordance with the recommendations beautician, taking into account individual especially user. Plug-in connector 36 is connected input voltage stabilizer 34 to output of source of direct current 32. Through with thermoelements of the massage blocks 1 and 2 direct current is passed, and due to effect of Peltier s is cooled teplokontaktnoi plate 8 (to 10-17about with). After preset time (for example, 1 min) pulse generator 35 automatically switches the direction of current, passed through with thermoelements of the massage blocks 1 and 2, and heating teplokontaktnoi plate (to 25-32about with). After 1 min pulse generator again changes direction of current and again cooling takes place teplokontaktnoi plate 8 and T. d. Total 7 session duration massage is usually 30-60 min. In the process of contrast thermal cycling occurs periodic tension (at heating) and compression (at cooling) of section of skin, located under teplokontaktnoi plate 8 and simultaneously changes the rate of metabolic processes in this section of skin and subcutaneous layers. Thus massage effect and at sufficient amount sessions massage (usually 20-30) due to stimulating effect on skin is gradual reduction depth of wrinkles on the skin up to complete their disappearance. Upon expiration of time, allotted per session massage, plug 36 voltage stabilizer 34 is disconnected from direct current source 32. For 2-3 min device continues to remain on the patient s head for gradual equalization of temperature teplokontaktnykh plates 8 with temperature of skin. Control effectiveness massage is accepted methods.

[DESC0007] In comparison with known device for local skin massage allows considerably increased efficiency of massage, since provides contrast thermal cycling at uniform thermal action on massiruemyi section. Without using surgical treatment is smoothing of wrinkles on the face of the up to complete their disappearance. Besides, device may be used not

only in conditions of cosmetic saloon, but and in various household conditions, for example in saloon car or at walking user.

CLMEN

[CLM0001] 1. Device for KRIOMASSAZhA , containing massage unit, including body, in which there are installed teplokontaktnaya plate, heat removal system and thermal members, and agent for heating or cooling thermocontact plate, including direct current source, connected through switching element to termoelementam , characterized in that, it is equipped with the unit of the automatic contrast thermal cycling, located between source of direct current and switching element, holder with hole for massage unit and members pressing teplokontaktnoi plate to skin, interacting with holder, also the latter is located on member pressing with the possibility of displacement along it.
[CLM0002] 2. Device according to Claim 1, characterized in that unit for automatic contrast thermal cycling is made in the form of series-connected voltage stabilizer and pulse generator, wherein the input voltage stabilizer is connected to the output of the source of direct current, and output pulse generator is connected to the commutation element.
[CLM0003] 3. Device according to Claim 1, characterized in that it is provided with the second identical located in holder massage unit, connected with first bridge.
[CLM0004] 4. Device according to Claim 1, characterized in that body massage unit is in hole holder pivotally.
[CLM0005] 5. Device according to Claim 1, characterized in that heat removal system of massage unit is installed in holder pivotally.
[CLM0006] 6. Device according to Claim 1, characterized in that teplokontaktnaya plate along the perimeter of the is fixed in supporting member, made of elastic material.
[CLM0007] 7. Device according to Claim 3, characterized in that members pressing are made in the form of headband from arc-shaped springs, end sections of which are located in slots of holders.
[CLM0008] 8. Device according to Claim 1, characterized in that unit for automatic contrast thermal cycling is installed in additional body, on face surface which is located regulator of automatic contrast thermal cycling.

KT

local skin massage; teplokontaktnykh plate; physical therapy apparatus; alyumoksidnoi ceramic; beryllium oxide; automatic contrast; massage face skin; holder massage; plate holder groove; heat removal system; teplokontaktnye plate; teplokontaktnuyu plate; series-connected voltage stabilizer; session duration massage; fixation massage block; switching element; element holder; body massage; hole holder; external spherical surface; convex spherical surface; semiconductor branch electronic conductivity; teplokontaktnaya plate; supporting element; arc-shaped spring; contrast thermal cycling; thermal member; galvanic element; curvilinear groove; input voltage stabilizer